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## Contents

|  |     |
|--|-----|
| Publisher's note   | vii |
| Corrigendum  | 1   |
| Scanning tunneling microscopy study of GaAs(1 0 0) surface prepared by HCl-isopropanol treatment<br>P. Laukkanen, M. Kuzmin, R.E. Perälä, R.-L. Vaara and I.J. Väyrynen  | 2   |
| Ti <sub>3</sub> SiC <sub>2</sub> formed in annealed Al/Ti contacts to p-type SiC<br>B. Pécz, L. Tóth, M.A. di Forte-Poisson and J. Vacas   | 8   |
| Surface segregation of lanthanum and cerium ions in ceria/lanthana solid solutions: comparison between experimental results and a statistical–mechanical model<br>M.F. Wilkes, P. Hayden and A.K. Bhattacharya | 12  |
| Adsorption properties for urokinase on local diatomite surface<br>Y. Yang, J. Zhang, W. Yang, J. Wu and R. Chen  | 20  |
| Ultra thin Al <sub>2</sub> O <sub>3</sub> films grown on Ni <sub>3</sub> Al(1 0 0)<br>V. Podgursky, I. Costina and R. Franchy  | 29  |
| Anodisation-related structural variations of porous silicon nanostructures investigated by photoluminescence and Raman spectroscopy<br>O. Ben Younes, M. Oueslati and B. Bessaïs                               | 37  |
| Continuous wave ultraviolet radiation induced frustration of etching in lithium niobate single crystals<br>S. Mailis, C. Riziotis, P.G.R. Smith, J.G. Scott and R.W. Eason                                     | 46  |
| Effect of plasma density on the distribution of incident ions and depth profile in plasma-based ion implanted layers<br>S. Qi, X. Lifang, M. Xinxin and S. Mingren   | 53  |
| Electron conduction mechanism of Si(1 0 0)/Ag and Si(1 0 0)/H/Ag<br>S. Iida, A. Hiraoka, H. Noritake, R. Tanaka and M. Yukawa  | 60  |
| The comparative characterization of structural hetero-geneity of mesoporous activated carbon fibers (ACFs)<br>P. Kowalczyk, V.M. Gun'ko, A.P. Terzyk, P.A. Gauden, H. Rong, Z. Ryu and D.D. Do                 | 67  |
| The influence of gas phase composition on the process of Au–Hg amalgam formation<br>T. Kobiela, B. Nowakowski and R. Duś   | 78  |
| Substrate temperature dependent structural, optical and electrical properties of spray deposited iridium oxide thin films<br>R.K. Kwar, P.S. Chigare and P.S. Patil  | 90  |
| Copper oxide reduction through vacuum annealing<br>S.Y. Lee, N. Mettlach, N. Nguyen, Y.M. Sun and J.M. White   | 102 |
| Nanotribology of MoS <sub>x</sub> coatings investigated by oscillating lateral force microscopy<br>X. Zhang and J.-P. Celis  | 110 |
| Changes in chemical behavior of thin film lead zirconate titanate during Ar <sup>+</sup> -ion bombardment using XPS<br>J.-N. Kim, K.-S. Shin, D.-H. Kim, B.-O. Park, N.-K. Kim and S.-H. Cho                   | 119 |
| The influence of some Arylazobenzoyl acetonitrile derivatives on the behaviour of carbon steel in acidic media<br>S.A. Abd El-Maksoud  | 129 |
| Phase transformation in room temperature pulsed laser deposited TiO <sub>2</sub> thin films<br>A.K. Sharma, R.K. Thareja, U. Willer and W. Schade  | 137 |

|   |     |
|---|-----|
| Study of stress effects in the oxidation of phosphated $\alpha$ -iron: in situ measurement by diffraction of synchrotron radiation<br>B. Panicaud, J.L. Grosseau-Poussard, P.O. Renault, J.F. Dinhut, D. Thiaudière and M. Gailhanou      | 149 |
| Titanium disilicide formation by rf plasma enhanced chemical vapor deposition and film properties<br>O.A. Fouad, M. Yamazato, H. Ichinose and M. Nagano   | 159 |
| Enhancement of field emission in carbon nanotubes through adsorption of polar molecules<br>M. Grujicic, G. Cao and B. Gersten   | 167 |
| High energy ion irradiation induced surface roughening in Ag and Cu films<br>A. Crespo-Sosa, M. Muñoz, J.-C. Cheang-Wong, A. Oliver, J.M. Sániger and J.G. Bañuelos   | 178 |
| Emission of $\text{CsM}^+$ clusters<br>Yu. Kudriavtsev, A. Villegas, A. Godines and R. Asomoza  | 187 |
| Influence of the working atmosphere on the excimer laser ablation of $\text{Al}_2\text{O}_3$ -TiC ceramics<br>M. Mendes and R. Vilar  | 196 |
| Angle-resolved X-ray photoelectron spectroscopy study of the oxides on Nb surfaces for superconducting r.f. cavity applications<br>Q. Ma and R.A. Rosenberg   | 209 |
| Ultrathin poly(ethylene glycol) films for silicon-based microdevices<br>S. Sharma, R.W. Johnson and T.A. Desai  | 218 |
| XPS study on double glow plasma corrosion-resisting surface alloying layer<br>J. Ai, J. Xu, F. He, X. Xie and Z. Xu   | 230 |
| Characterisation of pitting corrosion in sealed anodic films formed in sulphuric, sulphuric/molybdate and chromic media<br>V. Moutarlier, M.P. Gigandet and J. Pagetti  | 237 |
| Investigations on the chemical states of sintered barium titanate by X-ray photoelectron spectroscopy<br>S. Kumar, V.S. Raju and T.R.N. Kutty   | 250 |
| Surface chemical modification of silica aerogels using various alkyl-alkoxy/chloro silanes<br>A. Venkateswara Rao, M.M. Kulkarni, D.P. Amalnerkar and T. Seth   | 262 |
| Surface viscoelasticity studies of $\text{Gd}_2\text{O}_3$ , $\text{SiO}_2$ optical thin films and multilayers using force modulation and force-distance scanning probe microscopy<br>N.K. Sahoo, S. Thakur, M. Senthilkumar and N.C. Das | 271 |
| Electronic behaviour and field emission of metal-semiconductor-insulator-metal (MSIM) heterostructures based on a-C:H films<br>A. Foulani   | 294 |
| Full potential calculations on the electron bandstructures of Sphalerite, Pyrite and Chalcopyrite<br>R. Edelbro, Å. Sandström and J. Paul   | 300 |
| Preparation of nano-size particles of silver with femtosecond laser ablation in water<br>T. Tsuji, T. Kakita and M. Tsuji   | 314 |
| Chemical bonding of magnetron-sputtered copper on PECVD amorphous SiCOF film<br>S.-J. Ding, D.W. Zhang, J.-T. Wang and W.W. Lee   | 321 |
| Formation of monoatomic chains of metallic elements<br>Q. Jiang, M. Zhao and J.C. Li  | 331 |
| Dynamical thermal model for thin metallic film-substrate system with resistive heating<br>F. Avilés, A.I. Oliva and J.A. Aznárez  | 336 |
| Factors influencing phase compositions and structure of plasma sprayed hydroxyapatite coatings during heat treatment<br>Y.-P. Lu, Y.-Z. Song, R.-F. Zhu, M.-S. Li and T.-Q. Lei   | 345 |
| Removal efficiency of organic contaminants on Si wafer by dry cleaning using $\text{UV/O}_3$ and ECR plasma<br>K. Choi, S. Ghosh, J. Lim and C.M. Lee   | 355 |
| Author Index  | I   |
| Subject Index   | IV  |